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Front Matter: Volume 10091

, "Front Matter: Volume 10091," Proc. SPIE 10091, Laser Applications in Microelectronic and Optoelectronic Manufacturing (LAMOM) XXII, 1009101 (22 May 2017); doi: 10.1117/12.2276097

SPIE.

Event: SPIE LASE, 2017, San Francisco, California, United States

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Laser Applications in Microelectronic and Optoelectronic Manufacturing (LAMOM) XXII

**Beat Neuenschwander
Costas P. Grigoropoulos
Tetsuya Makimura
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Editors

**30 January–2 February 2017
San Francisco, California, United States**

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SPIE

Volume 10091

Proceedings of SPIE 0277-786X, V. 10091

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Laser Applications in Microelectronic and Optoelectronic Manufacturing (LAMOM) XXII, edited by
Beat Neuenschwander, Costas P. Grigoropoulos, Tetsuya Makimura, Gediminas Račiukaitis, Proc. of SPIE
Vol. 10091, 1009101 · © 2017 SPIE · CCC code: 0277-786X/17/\$18 · doi: 10.1117/12.2276097

Proc. of SPIE Vol. 10091 1009101-1

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Author(s), "Title of Paper," in *Laser Applications in Microelectronic and Optoelectronic Manufacturing (LAMOM) XXII*, edited by Beat Neuenschwander, Costas P. Grigoropoulos, Tetsuya Makimura, Gediminas Račiukaitis, Proceedings of SPIE Vol. 10091 (SPIE, Bellingham, WA, 2017) Seven-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781510606234

ISBN: 9781510606241 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA

Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

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Contents

vii	<i>Authors</i>
ix	<i>Conference Committee</i>

LASER PROCESSES I: THIN FILMS

10091 02	Laser processing of VO₂ thin films for THz devices and metamaterials (Invited Paper) [10091-1]
10091 04	Tailoring of graphite oxide electrical properties using laser irradiation [10091-3]
10091 05	Low temperature deposition of inorganic films by excimer laser assisted chemical vapor deposition [10091-4]
10091 06	Damage free Al doping on 4H-SiC with passivation films using XeF excimer laser irradiation in AlCl₃ acid solution [10091-5]

LASER PROCESSES II: PRODUCTION TECHNOLOGIES

10091 08	Co-propagating FWM of axial symmetric laser pulse with femtosecond duration [10091-14]
----------	---

LASER PROCESSES III: APPLICATIONS

10091 0B	Laser-assisted manufacturing of super-insulation materials [10091-10]
10091 0C	High speed, mask-less, laser controlled deposition of microscale tungsten tracks using 405 nm wavelength diode laser [10091-11]
10091 0D	Laser assisted hybrid additive manufacturing of thermoelectric modules [10091-12]
10091 0F	Laser processing for precise fabrication of the THz optics [10091-7]

ENABLING THROUGHPUT AND QUALITY SCALING

10091 0G	Throughput scaling by spatial beam shaping and dynamic focusing (Invited Paper) [10091-15]
10091 0H	Inline measurement for quality control from macro to micro laser applications (Invited Paper) [10091-16]
10091 0I	New random trigger-feature for ultrashort-pulsed laser increases throughput, accuracy and quality in micromachining applications [10091-17]

- 10091 OJ **Influence of the pulse duration and the experimental approach onto the specific removal rate for ultra-short pulses** [10091-18]

NANOSTRUCTURED OPTICAL FIBERS: JOINT SESSION WITH CONFERENCES 10091 AND 10094

- 10091 OK **FBG inscription in multimode microfiber via point-by-point radiation with femtosecond laser (Best Student Paper Award)** [10091-19]
- 10091 OL **Femtosecond-pulse inscription of fiber Bragg gratings in multimode graded index fiber** [10091-20]

SCRIBING TRANSPARENT MATERIALS: JOINT SESSION WITH CONFERENCES 10091 AND 10094

- 10091 ON **Modification of glass using an axicon-generated non-symmetrical Bessel-Gaussian beam** [10091-22]

ULTRAFAST LASERS FOR CHARACTERIZATION: JOINT SESSION WITH CONFERENCES 10091 AND 10094

- 10091 OR **Ultrafast laser energy deposition in copper revealed by simulation and experimental determination of optical properties with pump-probe ellipsometry** [10091-26]
- 10091 OS **Numerical study of the influence of picosecond laser spot size on laser ablation of metal for high laser fluence cases** [10091-27]

LASER PROCESSING WITH PLASMONICS: JOINT SESSION WITH CONFERENCES 10091 AND 10093

- 10091 OT **Nanograting formation in air through plasmonic near-field ablation induced by femtosecond laser pulses (Invited Paper)** [10091-28]

LASER GENERATED NANOSTRUCTURES: JOINT SESSION WITH CONFERENCES 10091 AND 10093

- 10091 OW **Direct printing of micro/nanostructures by femtosecond laser excitation of nanocrystals** [10091-31]

INDUSTRIAL APPLICATIONS: PROCESSES: JOINT SESSION WITH CONFERENCES 10091 AND 10094

- 10091 OZ **Ultrashort-pulsed laser material processing with high repetition rate burst pulses** [10091-34]
- 10091 IO **Studies on nanosecond 532nm and 355nm and ultrafast 515nm and 532nm laser cutting super-hard materials** [10091-35]

POSTER SESSION

- 10091 15 **Polycarbonate resin drilling by longitudinally excited CO₂ laser** [10091-40]
- 10091 19 **Temperature control of CO₂ laser glass melting for fiber processing technology** [10091-44]
- 10091 1B **Laser surface modification of ZnO for solar converters** [10091-46]
- 10091 1C **Beam shaping by spatial light modulator and 4f system to square and top-flat for interference laser processing (Best Student Poster Award)** [10091-47]
- 10091 1E **Ultrafast laser scribing of transparent conductive oxides in Cu(In,Ga)Se₂ solar cells via laser lift-off process: the control of laser-induced damage** [10091-49]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Afanasjev, Valentin, 1B	Minkevičius, Linas, 0F
Akitsu, Tetsuya, 15	Miyaji, Godai, 0T
Ammann, Hubert, 0I	Miyazaki, Noriaki, 1C
Asano, T., 06	Miyazaki, Kenzo, 0T
Auyeung, Raymond C. Y., 02	Mukhin, Nikolay, 1B
Babin, Sergey A., 0L	Nakamura, D., 06
Barkauskas, Jurgis, 04	Nakata, Yoshiki, 1C
Benetti, Marco, 0I	Narazaki, Aiko, 1C, 1E
Bergner, K., 0G	Nargelienė, Viktorija, 04
Breckenfeld, Eric, 02	Neuenschwander, Beat, 0I, 0J, 0S
Charipar, Kristin M., 02	Niaura, Gediminas, 04
Charipar, Nicholas A., 02	Niino, Hiroyuki, 1E
Dostovalov, Alexandr V., 0L	Niki, Shigeru, 1E
Dudutis, Juozas, 0N	Nishinaga, Jiro, 1E
Eyama, Takashi, 0O	Nolte, S., 0G
Flamm, D., 0G	Oehler, Andreas, 0I
Gečys, Paulius, 0N	O'Neill, William, 0C
Grishkanich, Aleksandr, 1B	Osawa, Kazuhito, 1C
Grossmann, D., 0G	Pan, Heng, 0W
He, Jiaji, 0K	Park, Byung Kyu, 0B
Hirsch, Sören, 1B	Park, Jongmin, 05
Hu, Di, 0K	Patel, Rajesh, 0X
Huber, Heinz P., 0R	Pichot, Jean Francois, 0H
Hwang, David J., 05, 0B, 0D	Piqué, Alberto, 02
Iakovlev, Alexey, 1B	Račiukaitis, Gediminas, 0F, 0N
Ikeda, A., 06	Rapp, Stephan, 0R
Ikenoue, H., 06	Redka, Dmitry, 1B
Indrišiūnas, Simonas, 0F	Remund, Stefan, 0I, 0J
Ishizuka, Shogo, 1E	Romano, Valerio, 0S
Jaeggi, Beat, 0I, 0J	Sato, Tadafake, 1E
Jebali, M. A., 19	Schmidt, Michael, 0R
Jitsuno, Takahisa, 15	Schoenleber, Martin, 0H
Kablukov, Sergey I., 0L	Schulze, Jochen, 0H
Kaiser, M., 0G	Shibata, Hajime, 1E
Kamikawa-Shimizu, Yukiko, 1E	Shoji, Tatsuya, 1C
Kašalynas, Irmantas, 0F	Shou, Wan, 0W
Kato, Masaya, 15	Šniaukas, Ramūnas, 0F
Kim, Heungsoo, 02	Sparkes, Martin, 0C
Kleiner, J., 0G	Suwa, A., 06
Kogel-Hollacher, Markus, 0H	Takada, Hideyuki, 1E
Kramer, T., 0J	Tao, Sha, 10
Kuchik, Igor E., 08	Ten, Jyi Sheuan, 0C
Kuk, Seungkuk, 05	Terukov, Evgeniy, 1B
Kumkar, M., 0G	Tewolde, Mahder, 0D
Lee, Woo Il, 0B	Torizuka, Kenji, 1E
Longtin, Jon P., 0D	Trofimov, Vyacheslav A., 08
Lukša, Algimantas, 04	Trusovas, Romualdas, 04
Mathews, Scott A., 02	Tsuboi, Yasuyuki, 1C
Mayerhofer, Roland, 0Z	Tsuchiya, T., 06

Uno, Kazuyuki, 15
Voisiat, Bogdan, 0F
Wang, Anbo, 0K
Wang, Brian, 10
Wang, Zhen, 0B
Wassermann, Dominique, 0I
Winter, Jan, 0R
Wolf, Alexey A., 0L
Xuan, Haifeng, 0K
Yang, Shuo, 0K
Yoshida, Masataka, 1C
Zhang, Jie, 10
Zhang, Tao, 05, 0B, 0D
Zhang, Yiming, 0S
Zhao, Jay, 10
Zimmermann, F., 0G
Zlobina, Ekaterina A., 0L

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- 1 Laser Processes I: Thin Films
Beat Neuenschwander, Berner Fachhochschule Technik und Informatik (Switzerland)
- 2 Laser Processes II: Production Technologies
Costas P. Grigoropoulos, University of California, Berkeley (United States)
- 3 Laser Processes III: Applications
Tetsuya Makimura, University of Tsukuba (Japan)
- 4 Enabling Throughput and Quality Scaling
Gediminas Račiukaitis, Center for Physical Sciences and Technology (Lithuania)
- 5 Nanostructured Optical Fibers: Joint Session with Conferences 10091 and 10094
Roberto Osellame, CNR-Istituto di Fotonica e Nanotecnologie (Italy)
- 6 Scribing Transparent Materials: Joint Session with Conferences 10091 and 10094
Peter R. Herman, University of Toronto (Canada)
- 7 Laser Interaction Dynamics: Joint Session with Conferences 10091 and 10094
Guido Hennig, Daetwyler Graphics AG (Switzerland)
- 8 Ultrafast Lasers for Characterization: Joint Session with Conferences 10091 and 10094
Jean-Philippe Colombier, Université Jean Monnet Saint-Etienne (France)
- 9 Laser Processing with Plasmonics: Joint Session with Conferences 10091 and 10093
David B. Geohegan, Oak Ridge National Laboratory (United States)

- 10 Laser Generated Nanostructures: Joint Session with Conferences 10091 and 10093
Theobald Lohmueller, Ludwig-Maximilians-Universität München (Germany)
- 11 Industrial Applications: Systems: Joint Session with Conferences 10091 and 10094
Eric P. Mottay, Amplitude Systèmes (France)
- 12 Industrial Applications: Processes: Joint Session with Conferences 10091 and 10094
Malte Kumkar, TRUMPF Laser- und Systemtechnik GmbH (Germany)